SEP 1 NFORMATION DISCLOSURE STATEMENT BY APPLICANT Application No. 10/705,360

Filing Date November 10, 2003

First Named Inventor Bulent M. Basol

Art Unit 1742

Examiner Harry D. Wilkins, III

Attorney Docket No. ASMNUT.027DVCP1

(Multiple sheets used when necessary)

SHEET 1 OF 3 Attorney Docket No. ASMNUT.027DV0

		•	U.S. PATENT	DOCUMENTS	
Examiner Initials	Cite No.	Document-Number Number - Kind Code (if known) Example: 1,234,567 B1	Publication Date MM-DD-YYYY	Name of Patentee or Applicant	Pages, Columns, Lines Where Relevant Passages or Relevant Figures Appear
HW	1	2,965,556	12/1960	Gudmund Damgaard Laurits	
	2	3,367,468	01/1972	Icxi et al.	
	3	3,448,023	06/1969	Bell Ramsay M	
	4	3,595,089	05/1976	Watts	*
	5	3,779,887	12/1973	Gildone	
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	7	4,024,029	05/17/1977	Rain et al.	
	8	4,391,684	07/1983	Goddard	
	9	4,431,5001	02/1984	Leppanen	
	10	4,466,864	08/1984	Bacon et al.	
	11	4,610,772	09/1986	Palnik	
	12	5,024,735	06/1991	Kadija	
	13	5,171,412	12/1992	Talieh et al.	
	14	5,429,733	07/1995	Ishida	
	15	5,558,568	09/1996	Talieh et al.	
	16	5,567,300	10/26/1996	Datta et al.	
	17	5,692,947	12/1997	Talieh et al.	
	18	5,700,366	12-1997	Steblianko et al.	
	19	5,755,859	05/1998	Brusic et al.	
	20	5,807,165	09/15/1998	Uzoh et al.	
	21	5,816,900	10/1998	Nagahara et al.	
	22	5,833,820	11/1998	Dublin	
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<b>W</b>	28	6,004,880	12/1999	Liu et al.	
HW	29	6,142,155	11/2000	Adams et al.	

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Date Considered

<sup>\*</sup>Examiner: Initial if reference considered, whether or not citation is in conformance with MPEP 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

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Examiner Initials	Cite No.	Document Number Number - Kind Code (if known) Example: 1,234,567 B1	Publication Date MM-DD-YYYY	Name of Patentee or Applicant	Pages, Columns, Lines Where Relevant Passages or Relevant Figures Appear
HW	30	6,074,546	06/13/2000	Sun et al.	
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	51	6,676,822 B1	01/13/2004	Talieh	
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HW	58	6,958,114 B2	10/25/2005	Talieh et al.	

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FOREIGN PATENT DOCUMENTS						
Examiner Initials	Cite No.	Foreign Patent Document Country Code-Number-Kind Code Example: JP 1234567 A1	Publication Date MM-DD-YYYY	Name of Patentee or Applicant	Pages, Columns, Lines Where Relevant Passages or Relevant Figures Appear	T¹
HW	59	DE 2008664	1 09/1971			
HW	60	DE 4324330	03/1994			
HW	61	JP 2000208443 A	07/28/2000	Sony Corp.		
HW	62	WO 01/32362 A1	05/10/2001	Philips Semiconductors Inc.		

NON PATENT LITERATURE DOCUMENTS				
Examiner Initials	Cite No.	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published.	T <sup>1</sup>	
HW	63	CONTOLINI et al., "Electrochemical Planarization for Multilevel Metallization," September 1994, pp. 2503-2510.		
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